

ABSTRACT OF THE DISCLOSURE

A negative resist composition comprises:

(A) an alkali-soluble resin;

(B) a compound capable of generating an acid upon irradiation with a radiation;

(C) a crosslinking agent capable of crosslinking by the action of an acid; and

(D) a solvent mixture containing: at least one solvent selected from the group A below; and at least one selected from the group consisting of the group B below and the group C below:

group A: a propylene glycol monoalkyl ether carboxylate;

group B: a propylene glycol monoalkyl ether, an alkyl lactate, an acetic ester, a chain ketone and an alkyl alkoxypropionate;

group C: a γ -butyrolactone, an ethylene carbonate and a propylene carbonate.